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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/755,154	01/09/2004	Kevin J. Moeggenborg	100141	9641	
29050 7	590 11/16/2006		EXAMINER		
STEVEN WESEMAN ASSOCIATE GENERAL COUNSEL, I.P. CABOT MICROELECTRONICS CORPORATION			UMEZ ERONINI, LYNETTE T		
			ART UNIT	PAPER NUMBER	
	COMMONS DRIVE	1765			
AURORA, IL	URORA, IL 60504 DAT		DATE MAILED: 11/16/2006	6	

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary		Application No.	Applicant(s)				
		10/755,154	MOEGGENBORG ET AL.				
		Examiner	Art Unit				
		Lynette T. Umez-Eronini	1765				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply							
A SHORT WHICHEN - Extensions after SIX (6 - If NO period - Failure to re Any reply re	ENED STATUTORY PERIOD FOR REPLY /ER IS LONGER, FROM THE MAILING DA of time may be available under the provisions of 37 CFR 1.13 ) MONTHS from the mailing date of this communication. d for reply is specified above, the maximum statutory period we sply within the set or extended period for reply will, by statute, exceived by the Office later than three months after the mailing ent term adjustment. See 37 CFR 1.704(b).	TE OF THIS COMMUNICATION  (6(a). In no event, however, may a reply be tin  (ill apply and will expire SIX (6) MONTHS from  cause the application to become ABANDONE	N. nely filed the mailing date of this communication. (D (35 U.S.C. § 133).				
Status							
1)⊠ Res	ponsive to communication(s) filed on 8/30/6	<u>06</u> .					
2a)⊠ This	This action is <b>FINAL</b> . 2b) This action is non-final.						
• —							
clos	ed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 4	53 O.G. 213.				
Disposition o	of Claims	·	·				
4)⊠ Clai	m(s) <u>1-23</u> is/are pending in the application.						
•	4a) Of the above claim(s) is/are withdrawn from consideration.						
·	S) Claim(s) is/are allowed.						
·	m(s) <u>1-3 and 14-22</u> is/are rejected.						
•	m(s) <u>4-13</u> is/are objected to.						
8) Clai	im(s) are subject to restriction and/or	r election requirement.					
Application F	Papers						
9) <u></u> The	specification is objected to by the Examine	r.					
10)⊠ The	10)⊠ The drawing(s) filed on <u>09 January 2004</u> is/are: a)⊠ accepted or b)□ objected to by the Examiner.						
Арр	licant may not request that any objection to the	drawing(s) be held in abeyance. Se	e 37 CFR 1.85(a).				
•	lacement drawing sheet(s) including the correct	•					
11)∐ The	oath or declaration is objected to by the Ex	aminer. Note the attached Office	e action or form PTO-152.				
Priority unde	er 35 U.S.C. § 119						
12)∐ Ackr	nowledgment is made of a claim for foreign	priority under 35 U.S.C. § 119(a	)-(d) or (f).				
a)□ A	_						
-	1. Certified copies of the priority documents have been received.						
	<ul> <li>2. Certified copies of the priority documents have been received in Application No</li> <li>3. Copies of the certified copies of the priority documents have been received in this National Stage</li> </ul>						
3		•	eu in uns ivational Stage				
* See t	application from the International Bureau he attached detailed Office action for a list		ed.				
0001	and distance dotained office design for differ	o. a.o doranda dopido not iduare					
Attachment(s)							
1) Notice of F	References Cited (PTO-892)	4) Interview Summary		•			
· <u> </u>	Oraftsperson's Patent Drawing Review (PTO-948) n Disclosure Statement(s) (PTO-1449 or PTO/SB/08)	Paper No(s)/Mail D  5) Notice of Informal F	Pate Patent Application (PTO-152)				
	s)/Mail Date	6) Other:	· · · · · · · · · · · · · · · · · · ·				

## **DETAILED ACTION**

## Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 1, 2, 3, 14-20, and 22 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sasaki et al. (EP 1 279 708 A1).

As to claims 1-3, 14-20, and 22, Sakai teaches a polishing composition that comprises: at least one abrasive; at least one organic compound such as polyoxyalkylene addition polymer (same as Applicants' polymer) as seen in formula (1) below and formula (3), which is diisobutyldimethylbutynediol polyoxyethylene glycol ether, is an example of formula (1); hydrogen peroxide (same as Applicants' oxidizing additive) and water (same as Applicants' carrier). (Abstract and [0033, 0075, and 0082]). The polyoxyalkylene addition polymer is represented by formula (1), wherein each  $R_1$  to  $R_6$  is H or a  $C_{1-10}$  alkyl group and m and n is a positive number from 1 to 20 (Abstract). Formula (3) shows more branching in formula (3).

$$R_3$$
  $R_4$   $HO - (C_2H_4O)_5 - CC \equiv CC - C_2(C_2H_4O)_4 - OH$ 
 $R_1O - (X)_{22} - CC \equiv CC - C_2(Y)_2 - OR_2$ 
 $R_3 - R_4$   $CH_2 - CH_2$ 
 $CH_3 - CH - CH_3$ 
 $CH_3 - CH_3$ 
formula (1)

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The above reads on,

A polishing system comprising:

- (a) a liquid carrier,
- (b) a polymer, and
- (c) a polishing pad, an abrasive, or a combination thereof, in claim 1; wherein the polymer is a polyglycerol ([0030-0032]), in claim 14;

wherein the polymer comprises surface functional groups selected from the group consisting of amines, amides, carboxylic acids, sulfonic acids, phosphonic acids, hydroxyl groups, salts thereof, and combinations thereof ([0030-0032]), in claim 15;

wherein the polymer has a molecular weight of about 1,000 to about 1,000,000 g/mol ([0033]), in claim 16;

wherein the molecular weight is about 2,000 to about 500,000 g/mol ([0033]), in claim 17; and

wherein the system comprises an abrasive suspended in the liquid carrier ([0051), in claim 20; and

further comprising one or more polishing additives selected from the group consisting of chelating or complexing agents, oxidizing agents, surfactants, anti-foaming agents, biocides, and combinations thereof [0048], in claim 22.

However, Sakai differs in failing to explicitly disclose a polymer having a branching of about 50%, 60% and 70% or greater, as recited respectively in claims 1-3;

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wherein the polymer comprises a highly branched core comprising monomer, wherein about 50% of more of the monomers within the highly branched core are branched, in claim 18; and

a viscosity that is about 70% or less in claim 19.

Sakai illustrates in formula (3), an example of polymers having many branched structures, is known. Using formula (3) as an example, wherein R<sub>1</sub> to R<sub>6</sub> is C<sub>1-10</sub> alkyl group and m and n is a positive number from 1 to 20, suggests a polymer backbone in which more branching is possible. Therefore, in the absence of unexpected result, the presently claimed polymer would obviously have been provided to one having ordinary skill in the art at the time the invention was made by selecting a polymer having a branching as taught by Sakai, including Applicants' specifically claimed degree of branching, for the purpose of suppressing recesses on copper wiring in polishing of a device (Sakai, [0040]).

3. Claims 21 is rejected under 35 U.S.C. 103(a) as being unpatentable over Sakai (EP '708 A1) as applied to claims 1-3, and 14-20 above, and further in view of Chou et al. (US-PGPUB 2002/0125461 A1).

Sakai differs in failing to disclose a polishing system wherein the system comprises an abrasive fixed to a polishing pad.

Chou teaches a polishing system can comprise a polishing pad wherein either an abrasive is suspended in the liquid portion of the polishing system or the abrasive can be fixed on a polishing pad ([0015-0017]).

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Chou illustrates a polishing system wherein the system comprises an abrasive fixed to a polishing pad is known. Hence, it would have been obvious to one having ordinary skill in the art at the time of the claimed invention to substitute Sakai's polishing pad with an abrasive fixed to a polishing pad as taught by Chou because both pads are seen as equivalent for the purpose of effecting a method of polishing semiconductor wafers and other substrates, such as memory disk and high dielectric constant films (Chou, [0026]).

## Allowable Subject Matter

- 4. Claims 4-13 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
- 5. The following is a statement of reasons for the indication of allowable subject matter: As to claims 4-13, the prior art of record taken alone or in combination fails to teach a polishing system that comprises a polymer selected from the group consisting of dendritic polymers, comb polymers, bottle-brush polymers, linear dendrimer diblock copolymers, linear-dendrimer triblock copolymers, random-branched polymers, copolymers thereof, and combinations thereof, in combination with the rest of the limitations of the claims.

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## Response to Arguments

Applicant's arguments filed 8/30/2006 have been fully considered but they are not persuasive. Applicant traverse the rejection of claims 1-3, 14-20, and 22 under 35 § U.S.C. 103(a) over Sakai et al. (EP 1 279708 A1) and claim 21 under 35 U.S.C. § 103(a) over Sakai (EP '708 A1) in view of Chou et al. (US PG-PUB 2002/0125461 A1) as failing to disclose and suggest a polymer having a degree of branching of about 50% or greater. (Remarks, page 3 of 5). Applicants argue Sakai discloses a polyoxyalkylene addition polymer having a total of 4 out of12 possible branch points, which is less than 50% branching as required by the claims. Applicants also argue Sakai provides no suggest motivation to modify the polymers disclosed by Sakai.

Applicants' arguments are acknowledged and unpersuasive. Although Applicants disclose, "... The degree of branching is equal to the number of branched sites divided by the total number of monomer sites that are capable of branching..." (Specification, [0023]) and "The degree of branching of a highly branched polymer can be determined by NMR spectroscopy" (Specification, [0024]), they have not provided a basis for determining the degree of branching of Sakai's polymer. If branching is determined from NMR activity, then what is Applicants basis for estimating Sakai's polymer having roughly 33% branching? In the absence of NMR data, how does Applicants know the degree of branching in a polymer? Since Sakai illustrates in formula (3) that a polymer having some degree of branching is known, then, it would have been obvious to one having ordinary skill in the art at the time the invention was made to select a polymer having a degree of branching as taught in the Sakai reference, including Applicants'

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specifically claimed degree of branching, for the purpose of suppressing recesses on

copper wiring in polishing of a device (Sakai, [0040]).

Applicants argue the basis by which process claims 1-22 and product claim 23 were classified and viewed as being distinct because "the process of using the product

as claimed can be practiced with another materially different product, such as a polymer

that does not require a degree of branching of 50% or more" makes it clear that the

Sakai '708 patent, which discloses a lesser degree of branching, fails to suggest degree

of branching of 50% or more. Applicants' arguments are acknowledged. However, the

claims 1-23 were not classified on the basis of the Sakai patent, but on the basis of

Applicants' claim language and information provided in the Specification.

Conclusion

7. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time

policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE

MONTHS from the mailing date of this action. In the event a first reply is filed within

TWO MONTHS of the mailing date of this final action and the advisory action is not

mailed until after the end of the THREE-MONTH shortened statutory period, then the

shortened statutory period will expire on the date the advisory action is mailed, and any

extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of

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the advisory action. In no event, however, will the statutory period for reply expire later

than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Lynette T. Umez-Eronini whose telephone number is

571-272-1470. The examiner is normally unavailable on the First Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Nadine Norton can be reached on 571-272-1465. The fax phone number

for the organization where this application or proceeding is assigned is 571-273-8300.

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**OPERVISORY PATENT EXAMINER** 

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November 3, 2006